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(54) Title: A PROCESS OF CONTROLLED RADICAL GRAFTING OF A POLYOLEFIN

(57) Abstract: The present invention relates to a controlled radical grafting process of a polyolefin derived from monomeric units including a olefins. This process comprises the reaction of the polyolefin and at least one radical reaction initiator with a grafting system which comprises at least one grafting compound having an electron donator heterocyclic aromatic ring conjugated to at least one -HC=CR1R2 group in which at least one of R₁ and R₂ is an electron acceptor functional be performed continuously in an extruder or discontinuously in a mechanical mixer.